

(b) Amendments to the Claims

Please cancel claims 7-9 without prejudice or disclaimer and add new claims 10 and 11 as follows. A detailed listing of all the claims that are or were on the application is provided.

1. - 9. (Cancelled)

10. (New) A method of forming a deposited film in a system having:

- (i) a source for supplying a source gas into a chamber for forming a deposited film on a substrate;
- (ii) a plurality of shut-off valves provided in series between a non-reactive gas source and the chamber for introducing a non-reactive gas into the chamber for returning pressure within the chamber to atmospheric pressure; and
- (iii) at least one of a pressure gauge or an evacuating means provided between the plurality of shut-off valves, comprising:
  - (a) reducing pressure between the plurality of shut-off valves to facilitate detection of gas leakage in the shut-off valves;
  - (b) closing the plurality of shut-off valves; and
  - (c) while the shut-off valves are closed, supplying the source gas into the chamber to form the deposited film.

11. (New) The method according to claim 10, wherein a space between the plurality of shut-off valves is filled with the non-reactive gas to perform film deposition.